III.D FOURIER IMAGE PROCESSING TECHNIQUES

III.D.2 Optical Filtering

Introduction

History:

Independently introduced by Klug and DeRosier (1966) and Bancroft, Hills and Markham (1967)

- Only suitable for study of **periodic** specimens with **translational** symmetry

Main advantage:

Provides simple way to **remove contributions from noise** in micrographs (reveal clearer images of specimen structure)

- Also a powerful method for separating Moire images of multilayered specimens
- Principle of technique is quite straightforward
- In practice, method can *easily* lead to erroneous results

III.D.2 Optical Filtering III.D.2.a Indexing the Optical Diffraction Pattern

- First and *most important* step of filtering experiment
- Have to distinguish spots arising from noise (aperiodic image details) from those attributed to the periodic nature of the specimen

Correct filtration requires knowledge of how noise and signal components are distinguished

For most crystalline specimens:

- OD pattern is a lattice of strong spots (Bragg reflections) against a weaker background of noise
- Noise generally produces spots in all parts of OD pattern

III.D.2 Optical Filtering III.D.2.a Indexing the Optical Diffraction Pattern

Periodic noise:

- Appears at or close to the lattice points of the diffraction pattern
- *Cannot* be removed by filtering
- Systematic specimen flattening or staining artifacts are examples of situations which produce periodic-type noise

Characteristic "cross" observed in many OD patterns:

- Arises from edges of mask used to isolate portion of micrograph
- Mask creates an artificially high contrast border (window)

III.D.2.a Indexing the Optical Diffraction Pattern



OD and Filtration of Negatively-stained Phosphorylase b Crystal

From Kiselev et al., (1971) Plate III

III.D.2 Optical Filtering III.D.2.b Filtering Procedure

Filter mask:

- Designed with holes positioned to allow unobstructed passage of diffraction spots at lattice points (or lattice lines, *e.g.* for helical particles)

Position of filter mask:

- **Must be accurately positioned** in the diffraction plane of the OD so all spots at the lattice points are allowed through
- **Opaque** regions of mask **block** out most of **noise** in the OD pattern arising from non-periodic image features

Reconstruction lens:

- Placed **behind** the mask
- Refocuses unobstructed rays and forms a filtered image
- UNfiltered image formed if mask not present

III.D.2 Optical Filtering III.D.2.b Filtering Procedure

Optical reconstruction illustrates the Abbe double-diffraction phenomena of image formation

1st stage: OD pattern of the micrograph is formed (forward transformation)

2nd stage: reconstruction lens rediffracts the diffracted rays (back- or reverse transformation) to form an image (filtered or unfiltered)

- A filtered/unfiltered image is result of rediffraction of masked/unmasked diffraction pattern of micrograph

III.D.1 Optical Diffraction III.D.1.b Experimental Apparatus





Adapted from Slayter, Fig. 19-12a, p.448

III.D.2 Optical Filtering III.D.2.c Experimental Apparatus



Adapted from Slayter, Fig. 19-12b, p.448

Optical filtering **reduces image noise** by **averaging** unit cells in the periodic array

- As **size of holes** in filter mask is **reduced**, more noise in the diffraction pattern is removed and the **extent of local averaging increases**

WARNING: If holes are made smaller than the diffraction spots, the signal-to-noise ratio may decrease

III.D.2 Optical Filtering



OD and Filtration of Negatively-stained Teven Polyheads

From Steven et al., (1976) Figs. 1 and 5, pp.192 and 200

III.D.2 Optical Filtering Optical Filtration of Negatively-stained T4 Polyhead



III.D.2 Optical Filtering

Optical Diffraction of Perfect and Imperfect 'Crystals'



Demonstration of how periodicity can be enforced on a structure by action of mask in Fourier space

III.D.2 Optical Filtering Optical Filtration of 'Imperfect Crystal'

Mask $(d_{a^*}/_{a^*} = 0.43)$



FT of Mask





Mask ($d_{a^*}/_{a^*} = 0.1$)



FT of Mask



From Baker thesis (1976) Fig. B.2

III.D.2 Optical Filtering Optical Filtration of 'Imperfect Crystal'



Masked transform = MASK X CRYSTAL TRANSFORM



Masked FT ($d_{a^*}/_{a^*} = 0.43$)



Masked FT ($d_{a^*}/_{a^*} = 0.2$)



Masked FT ($d_{a^*}/_{a^*} = 0.1$)

From Baker thesis (1976) Fig. B.2

III.D.2 Optical Filtering Optical Filtration of 'Imperfect Crystal' Masked transform = MASK X CRYSTAL TRANSFORM



III.D.2 Optical Filtering Optical Filtration of 'Imperfect Crystal'







III.D.2 Optical Filtering



Optical Filtering of Double Layer Crystal

Negatively-stained T-layer from Bacillus brevis

From Misell (1978) Fig. 4.19, p.163

III.D.2 Optical Filtering Optical Filtering of Imperfect 'Crystal'



Demonstration of how periodicity can be enforced on a structure by action of mask in Fourier space

III.D.2 Optical Filtering

Optical Filtering of Negatively Stained Catalase Crystal



KEY CONCEPT:

- Averaging results when an image is *convoluted* with the *transform* of the filter mask:

Reconstructed image = image $* T^{-1}(MASK)$

Reconstructed image = image * T⁻¹(MASK)

$$MASK = [LATTICE * HOLE] \times WINDOW$$

$$\int_{-1}^{-1} (MASK) = [LATTICE * HOLE] \times window$$

where,

Т

- lattice = specimen lattice (better be or else!)
- hole = Airy disk (if HOLE is a circle): determines extent of averaging

window $= \sin(X)/X$ "cross" (if WINDOW is a rectangle)

Reconstructed image = image * T⁻¹(MASK)

where,

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window $= \sin(X)/X$ "cross" (if WINDOW is a rectangle)

III.D.2 Optical Filtering III.D.2.f Artifacts of Optical Filtering

Sources of artifacts:

- Misindexed OD pattern ---> incorrect mask design
- **Incorrect positioning** of mask in diffraction plane causes wanted spots to be partially or totally blocked
- Mispositioned or misshaped mask holes make it impossible to pass all spots through the mask simultaneously